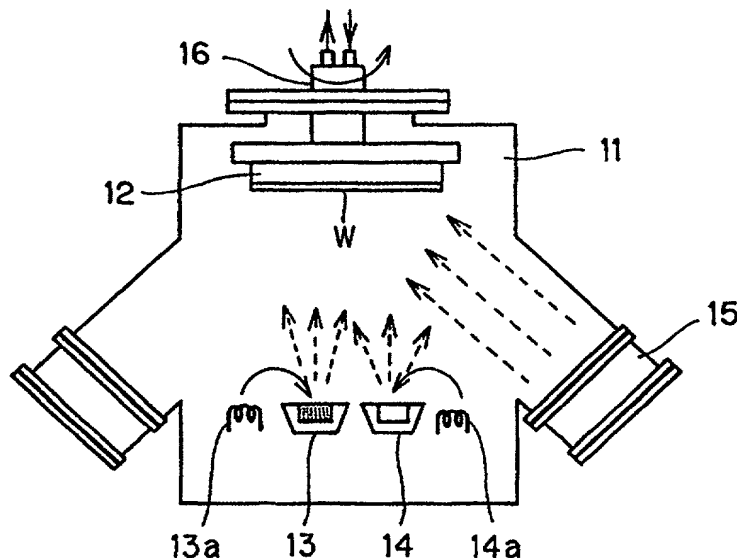




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(54) Title: SLIDING MEMBER AND MANUFACTURING METHOD THEREFOR



(57) Abstract

This invention relates to a hard coating developed for applications involving high-temperature corrosion by improving the performance of TiN coatings while retaining the superior wear resistance and low friction coefficient of TiN itself. The nitride-based sliding material has a face-centered cubic crystalline structure with lattice constant of between 0.414 and 0.423 nm, and is made of mostly TiN but contains at least one element selected from the group containing Al, Cr, Zr and Hf; or comprises a nitride-based material containing substantially titanium nitride and at least one element selected from a group consisting of B and Si, and having a face-centered cubic crystalline structure comprising crystallites of an average size of not more than 9 nm.